Atomic Layer Deposition Applications 10

Editors:

F. Roozeboom
Eindhoven University of Technology
and
TNO Eindhoven
Eindhoven, The Netherlands

S. De Gendt
IMEC
and
Catholic University (KU Leuven)
Leuven, Belgium

A. Delabie
IMEC
and
Catholic University (KU Leuven)
Leuven, Belgium

J. W. Elam
Argonne National Laboratory
Argonne, Illinois, USA

A. Londergan
Qualcomm Technologies, Inc.
Santa Clara, California, USA

O. van der Straten
IBM Research
Albany, New York, USA

Sponsoring Divisions:

Dielectric Science & Technology

Electronics and Photonics

Published by
The Electrochemical Society
65 South Main Street, Building D
Pennington, NJ 08534-2839, USA
tel 609 737 1902
fax 609 737 2743
www.electrochem.org

ecs transactions ™

Vol. 64, No. 9

Published by:

The Electrochemical Society
65 South Main Street
Pennington, New Jersey 08534-2839, USA

Telephone 609.737.1902
Fax 609.737.2743
e-mail: ecs@electrochem.org
Web: www.electrochem.org

ISSN 1938-6737 (online)
ISSN 1938-5862 (print)
ISSN 2151-2051 (cd-rom)

ISBN 978-1-62332-189-5 (Hard Cover)
ISBN 978-1-60768-546-3 (PDF)

Printed in the United States of America.

***ECS Transactions*, Volume 64, Issue 9**
Atomic Layer Deposition Applications 10

Table of Contents

Chapter 3
Molecular Layer Deposition

Chapter 4
Advanced Semiconductor Applications

Chapter 5
New ALD Materials and Processes

Chapter 8
Energy Applications

Chapter 9
Plasmonics/Closing Remarks